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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTORNEY'S DKT No. 027557-061	APPLICATION No. 09/928,491
	APPLICANT Stefan ANDERSSON	
	FILING DATE August 14, 2001	GROUP 2131

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U.S. PATENT DOCUMENTS				
Examiner Initials	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication (MM-DD-YYYY)
	Number	Kind Code (if known)		
JW	6,061,346		Nordman	May 9, 2000
JW	5,778,071		Caputo et al.	July 7, 1998
JW	5,784,463		Chen et al.	July 21, 1998
JW	5,943,423		Muftic	August 24, 1999
JW	6,041,409		Zunquan	March 21, 2000

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Foreign Patent Document		Country	Date of Publication (MM-DD-YYYY)	Translation	
	Number	Kind Code (if known)			Yes	no
JW	WO00/56105		PCT	September 21, 2000		
JW	WO01/22760		PCT	March 29, 2001		
JW	WO01/17310		PCT	March 8, 2001		
JW	EP0898397A2		Europe	February 24, 1999		
JW	WO00/45241		PCT	August 3, 2000		
JW	WO00/25546		PCT	May 4, 2000	Abstract	
JW	WO99/35553		PCT	July 15, 1999		

NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
	"Entity Authentication Using Public Key Cryptography", Federal Information Processing Standards Publication FIPS PUB 196 of February 1997, U.S. Department of Commerce/National Institute of Standardss and Technology.
JW	Document on AU-System WAP Browser.
JW	WAP Whitepaper from AU-System, February 1999.

Examiner Signature 	Date Considered 2-7-05
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SEND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.

